

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	35	"257"/\$.ccls. and (trenches or grooves or open\$4 or aperture or holes) and liner and (cvd or (chemical adj vapor adj depostion)) and (different adj (deep or depth)) and @ad<="20020402"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/20 09:47
L2	35	"257"/\$.ccls. and (trenches or via) and liner and (cvd or (chemical adj vapor adj depostion)) and (different adj (deep or depth)) and @ad<="20020402"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/20 06:34
L3	45	damascene and (depth or deep) and liner and (buried adj oxide) and semiconductor	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/20 08:19
L4	1261	(dual adj damascene) and liner and semiconductor	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/20 08:20
L5	251	((dual adj damascene) with liner) and semiconductor	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/20 08:20
L13	1396	(257/751).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/20 09:47
L14	115	"257"/374,774,775,751.ccls. and (trenches or grooves or open\$4 or aperture or holes) and liner and (cvd or (chemical adj vapor adj depostion)) and @ad<="20020402"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/20 12:41
L16	96	"257"/374,774,775,751.ccls. and (trenches or grooves or open\$4 or aperture or holes) and liner and (cvd or (chemical adj vapor adj depostion)) and @ad<="20010728"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/20 09:49

L17	740	(257/775).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/20 11:27
L23	2337	(257/774).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/20 12:40
L24	0	("257"/374,774,775,751.ccls. and (trenches or grooves or open\$4 or aperture or holes) and liner and (cvd or (chemical adj vapor adj depostion))).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/20 12:41
L25	0	("257"/374,774,775,751.ccls. and (trenches or grooves or open\$4 or aperture or holes) and liner and (cvd or (chemical adj vapor adj depostion))).clm.	US-PGPUB	OR	ON	2005/09/20 12:41
L26	282722	lee.in.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/20 12:49
L27	41	26 and (tae-jung)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/20 12:44
L28	251936	kim.in.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/20 12:49
L29	65	28 and (byung-sun)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/20 12:58
L30	23952	oh.in.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/20 12:57

L31	12	30 and (myoung-hwan)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/20 12:57
L32	20221	yoo.in.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/20 12:58
L33	4	31 and (seung-han)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/20 12:57
L34	49860	shin.in.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/20 12:58
L35	19	34 and (myung-sun)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/20 12:59
L36	112477	park.in.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/20 12:59
L37	62	36 and (sang-wook)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/20 12:59
L38	413	(257/374).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/20 13:02

L39	2724	(257/347).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/20 13:28
L40	152	(257/507).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/20 13:29
S1	1	("6440770").PN.	USPAT; USOCR	OR	OFF	2004/01/08 13:26
S15	8	((("6417073") or ("6316329") or ("6165822") or ("6083808") or ("4222792") or ("6479368") or ("6403446") or ("6358796")).PN.	USPAT; USOCR	OR	OFF	2005/09/20 08:45
S18	57	(trenches or grooves or open\$4 or aperture or holes) and liner and (cvd or (chemical adj vapor adj deposition)) and (different adj (deep or depth))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/01/10 08:35
S19	3	438/403,404,405,407,424,426, 427,428,437,435.ccls. and (trenches or grooves or open\$4 or aperture or holes) and liner and (cvd or (chemical adj vapor adj deposition)) and (different adj (deep or depth))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/19 13:49
S20	40	((trenches or grooves or open\$4 or aperture or holes) and liner and (cvd or (chemical adj vapor adj deposition)) and (different adj (deep or depth))) and semiconductor	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2003/05/15 08:40
S23	16	damascene and (depth or deep) and liner and (buried adj oxide) and semiconductor	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/20 06:36
S24	0	(damascene same (buried adj oxide) same (depth or deep) same liner) and semiconductor	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2003/05/15 08:43
S25	16	damascene and (buried adj oxide) and (depth or deep) and liner and semiconductor	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/19 14:08

S26	5	(trenches or grooves or open\$4 or aperture or holes) and (buried adj oxide) and liner and ((different or difference) adj (deep or depth)) and semiconductor	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/19 14:03
S27	59	(trenches or holes) and (buried adj oxide) and liner and (deep or depth) and semiconductor	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/19 14:08
S28	455	damascene and (depth or deep) and liner and semiconductor	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2003/05/15 09:24
S29	8	((("6448655") or ("6440843") or ("6071810") or ("6469336") or ("6365453") or ("6482735") or ("6057231") or ("6054768"))).PN.	USPAT; USOCR	OR	OFF	2005/06/20 13:04
S30	1	("20030020117").PN.	US-PGPUB; USOCR	OR	OFF	2004/01/07 13:26
S31	9	((("438"/\$.ccls. and (oxygen or ("o. sub.2")))) and @ad<="20020402" and trenches and (liner same CVD)) and (first adj trench) and (second adj trench)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/24 07:58
S32	8	((("438"/\$.ccls. and (oxygen or ("o. sub.2")))) and @ad<="20020402" and trenches and (liner same CVD)) and ((first adj trench) same (second adj trench))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/01/06 07:15
S33	84	(438/404,405,407,424,427,428, 437,435.ccls. and (oxygen or ("o. sub.2")))) and @ad<="20020402" and trenches and (liner same CVD)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/01/08 09:55
S34	306	("438"/\$.ccls. and (oxygen or ("o. sub.2")))) and @ad<="20020402" and trenches and (liner same CVD)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/01/08 09:55
S35	2033	(257/347).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/20 13:28

S36	301	("257"/\$.ccls. and (oxygen or ("o. sub.2")))) and @ad<="20020402" and trenches and (liner same CVD)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/01/08 09:55
S37	4	(257/347.ccls. and (oxygen or ("o. sub.2")))) and @ad<="20020402" and trenches and (liner same CVD)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/01/08 09:55
S38	5	((("6417073") or ("6316329") or ("6165822") or ("6083808") or ("4222792")).PN.	USPAT; USOCR	OR	OFF	2002/11/27 10:17
S40	1	("20020020840").PN.	US-PGPUB; USOCR	OR	OFF	2004/01/06 07:42
S41	1	("20030216016").PN.	US-PGPUB; USOCR	OR	OFF	2004/01/07 13:26
S42	146	(257/507).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/09/20 13:29
S43	2416	(257/347).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/01/10 08:16
S44	1	("6737706").PN.	USPAT; USOCR	OR	OFF	2005/01/10 07:41
S46	2	("6144079").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/01/10 08:16
S47	10	438/403,404,405,407,424,426, 427,428,437,435.ccls. and (trenches or grooves or open\$4 or aperture or holes) and liner and (cvd or (chemical adj vapor adj depostion)) and (different adj (deep or depth))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/20 12:43
S48	58	"438"/\$.ccls. and (trenches or grooves or open\$4 or aperture or holes) and liner and (cvd or (chemical adj vapor adj depostion)) and (different adj (deep or depth))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/20 12:43

S49	32	"438"/\$.ccls. and (trenches or grooves or open\$4 or aperture or holes) and liner and (cvd or (chemical adj vapor adj depostion)) and (different adj (deep or depth)) and @ad<="20020402"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/20 13:19
S50	35	"257"/\$.ccls. and (trenches or grooves or open\$4 or aperture or holes) and liner and (cvd or (chemical adj vapor adj depostion)) and (different adj (deep or depth)) and @ad<="20020402"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/20 06:30
S51	5	438/403,404,405,407,424,426, 427,428,437,435.ccls. and (trenches or grooves or open\$4 or aperture or holes) and liner and (cvd or (chemical adj vapor adj depostion)) and (different adj (deep or depth)) and @ad<="20020402"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/20 12:44
S53	1	("6872604").PN.	USPAT; USOCR	OR	OFF	2005/06/24 08:28
S54	1807	"438"/\$.ccls. and @ad<="20020402" and trenches and liner	US-PGPUB; USPAT	OR	ON	2005/06/24 08:41
S55	68	"438"/\$.ccls. and @ad<="20020402" and trenches and (liner with thicker)	US-PGPUB; USPAT	OR	ON	2005/06/24 08:13
S56	105	"438"/\$.ccls. and @ad<="20020402" and trenches and (liner same thicker)	US-PGPUB; USPAT	OR	ON	2005/06/24 08:05
S57	27	"438"/\$.ccls. and @ad<="20020402" and trenches and (liner near thicker)	US-PGPUB; USPAT	OR	ON	2005/06/24 08:08
S58	526	(dual adj damascene) and @ad<="20020402" and trenches and liner	US-PGPUB; USPAT	OR	ON	2005/06/24 08:07
S59	2	(dual adj damascene) and @ad<="20020402" and trenches and (liner near thicker)	US-PGPUB; USPAT	OR	ON	2005/06/24 08:08
S60	9	(dual adj damascene) and @ad<="20020402" and trenches and (liner with thicker)	USPAT	OR	ON	2005/06/24 08:09
S61	22	(dual adj damascene) and @ad<="20020402" and trenches and (liner same thicker)	USPAT	OR	ON	2005/06/24 08:09
S62	1	("6737706").PN.	USPAT; USOCR	OR	OFF	2005/09/20 12:44

S63	1	("6383920").PN.	USPAT; USOCR	OR	OFF	2005/06/24 08:49
S65	10	438/403,404,405,407,424,426, 427,428,437,435.ccls. and (trenches or grooves or open\$4 or aperture or holes) and liner and (cvd or (chemical adj vapor adj deposition)) and (different adj (deep or depth))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/19 13:57
S68	0	(438/403,404,405,407,424,426, 427,428,437,435.ccls. and (trenches or grooves or open\$4 or aperture or holes) and liner and (cvd or (chemical adj vapor adj deposition)) and (different adj (deep or depth))).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/19 13:58
S69	0	(438/403,404,405,407,424,426, 427,428,437,435.ccls. and (trenches or grooves or open\$4 or aperture or holes) and liner and (cvd or (chemical adj vapor adj deposition)) and (different adj (deep or depth))).clm.	US-PGPUB	OR	ON	2005/09/19 13:58
S70	0	("438"/\$.ccls. and (trenches or grooves or open\$4 or aperture or holes) and liner and (cvd or (chemical adj vapor adj deposition)) and (different adj (deep or depth))).clm.	US-PGPUB	OR	ON	2005/09/19 13:58
S71	13	(trenches or grooves or open\$4 or aperture or holes) and (buried adj oxide) and liner and ((different or difference) adj (deep or depth)) and semiconductor	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/19 14:03
S72	45	damascene and (buried adj oxide) and (depth or deep) and liner and semiconductor	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/19 14:09
S73	180	(trenches or holes) and (buried adj oxide) and liner and (deep or depth) and semiconductor	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/09/19 14:09
S74	1	("6627484").PN.	USPAT; USOCR	OR	OFF	2005/09/19 14:28